

# TARGET Waveform sampler for SiPM

- Using **TARGET** for single photon detection and precise timing:

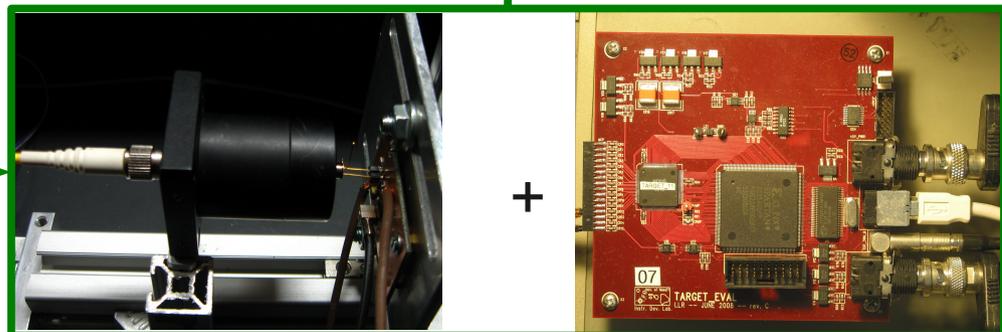
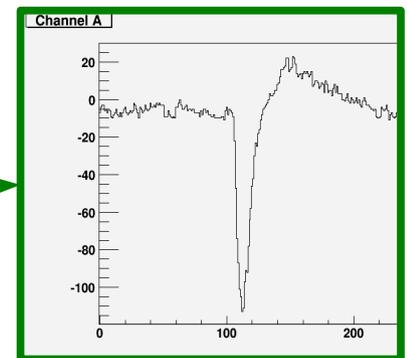
- Test fast preamplifier ( $\mu$ PC2710TB) with different inductors (0.047  $\mu$ H, 1  $\mu$ H & 22 $\mu$ H)
- Compare different Hamamatsu SiPM's:
  - \_ 3x3 mm; 100  $\mu$ m pitch; model S10931-100P(X); Serial # 19;  $V_{op} = 69.82$  V
  - \_ 1x1 mm; 25  $\mu$ m pitch; model S10362-11-025C; Serial # 34;  $V_{op} = 71.67$  V
  - \_ 1x1 mm; 100  $\mu$ m pitch; model S10362-11-100U; Serial # 147;  $V_{op} = 70.52$  V

- Compare different operating Voltages

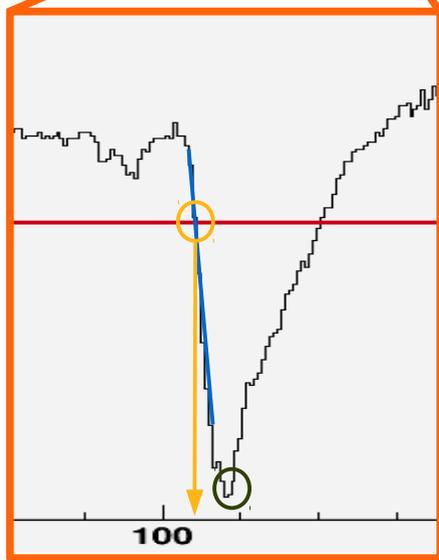
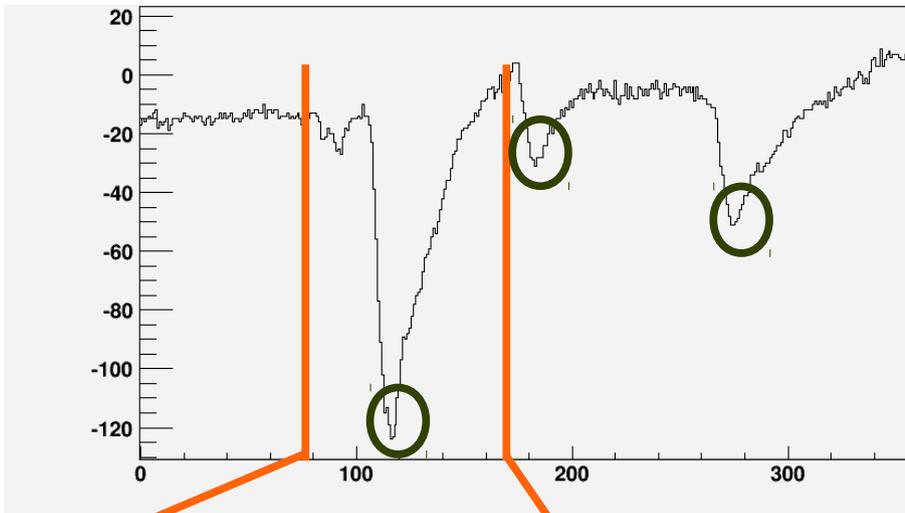
- Compare different light intensities (Filters  $\rightarrow$  6.25%; 12.5%; 50%)

## Setup:

- Laser, filters, diffuser  $\rightarrow$  small # of photons hit SiPM
- *Attenuator + Ortec fast amplifier for the 3x3 mm SiPM*



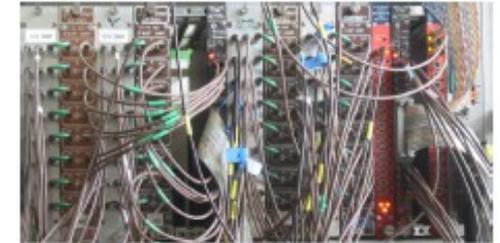
# Basic Waveform Analysis



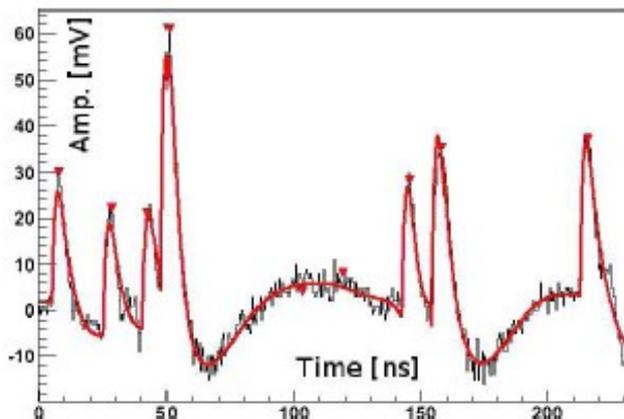
- 1) Baseline compensation
- 2) Look for peaks, I use ROOT TSpectrum
- 3) Only select peaks in a certain time window
- 4) @ this moment I only allow 1 peak for further analysis
- 5) Use a simplified CFD for time determination:
  - a) Get peak height
  - b) 30% of peak height = threshold
  - c) Lin fit around crossing of threshold determines the time of detection
- 6) Histogram peak heights and time

# TARGET Waveform Analysis of SiPM signals

- Digital sampling of electronic signal:
  - Switched Capacitor Array (SCA) stores total signal
  - Charge on each capacitor is measured → sampled waveform
  - Rebuild waveform for testing (**slow readout**)
  - Analyse waveform on FPGA (**fast readout**)
- Very POWERFULL tool because:
  - Incorporate waveform analysis algorithms on FPGA for deconvolution of piled-up signals (**classic-electronics**)
  - QDC and TDC all in 1 device!
  - High density of channels, cheap (VLSI), fast (up to 20 GSa/s), FPGA → flexible, low power



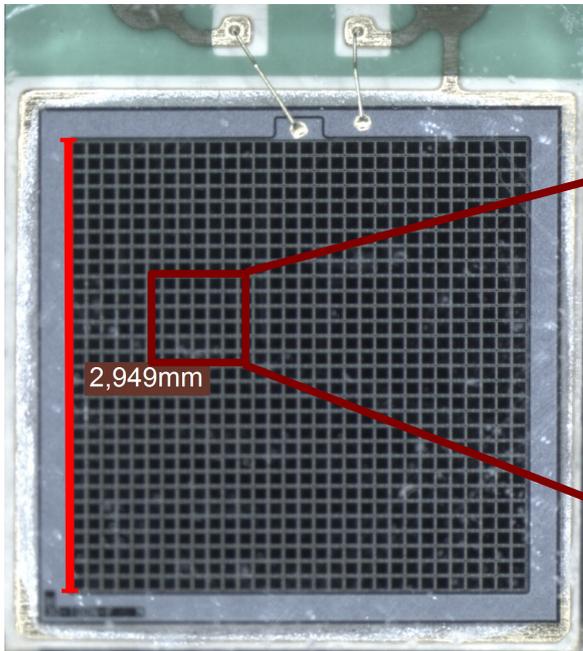
V.S.



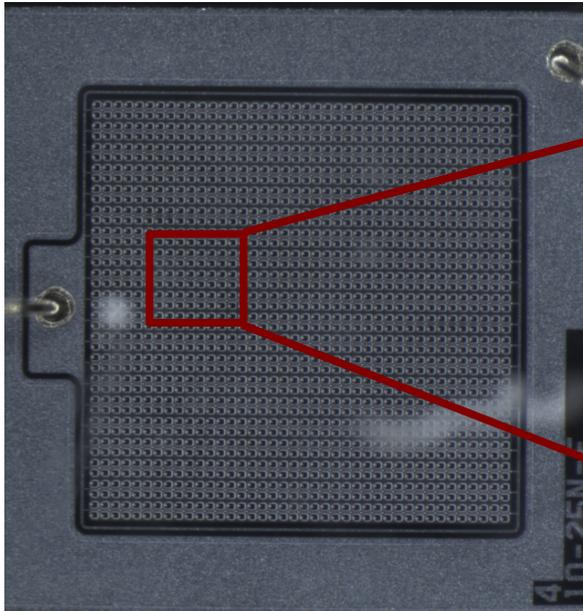
Fitfunction is based on a preamplifier & differentiator combination

$$V = \frac{Q_{in}}{C_f} \cdot \frac{1}{\tau_f - \tau_d} \cdot \left[ \exp\left(-\frac{t}{\tau_d}\right) - \frac{\tau_d}{\tau_f} \exp\left(-\frac{t}{\tau_f}\right) \right]$$

# SiPM Optical pictures

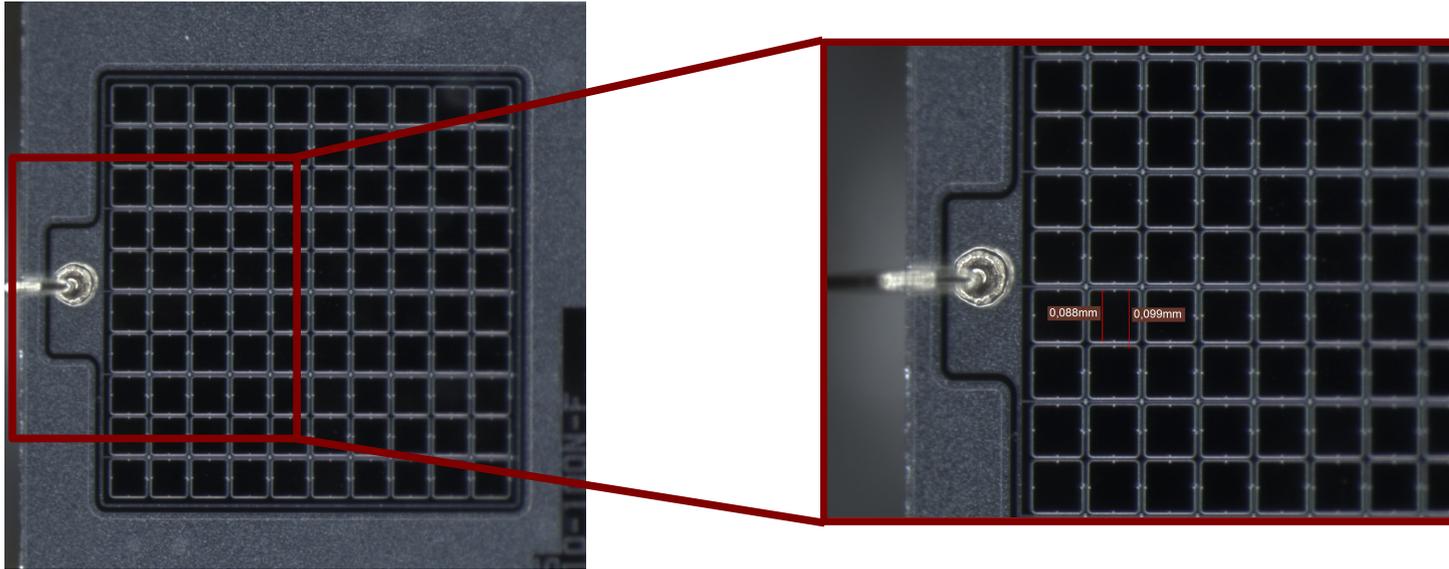


- Hamamatsu 3x3 mm<sup>2</sup>:
- 100 micron pitch
  - ~ 84 micron cell size



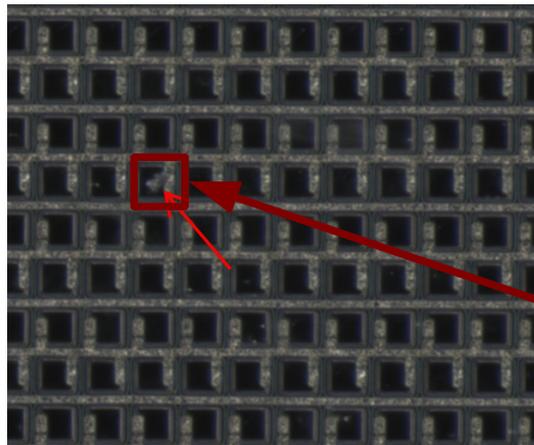
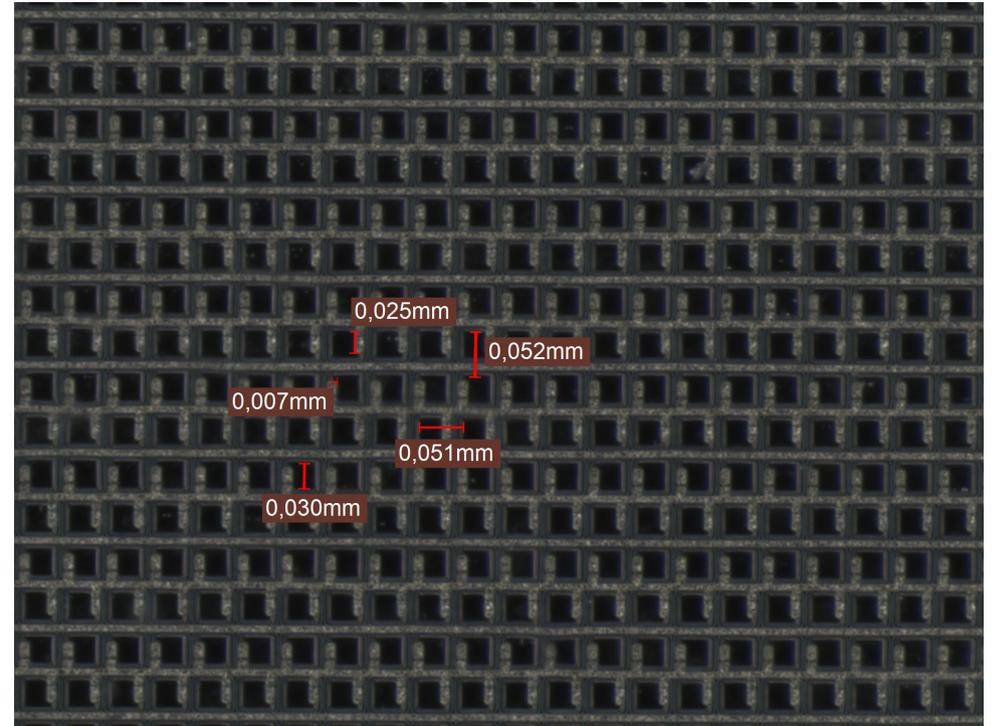
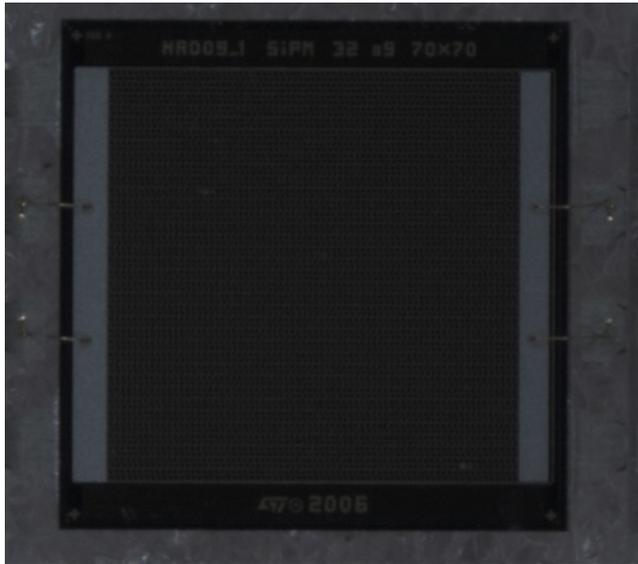
- Hamamatsu 1x1 mm<sup>2</sup>:
- 25 micron pitch
  - ~ 13 micron cell size

# Optical pictures



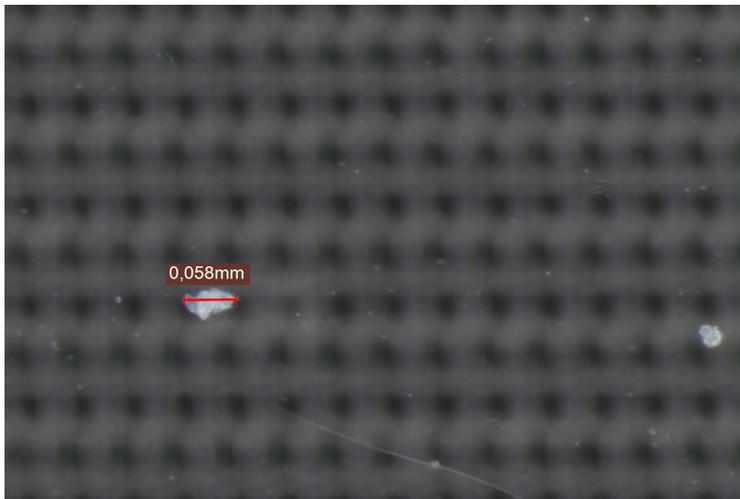
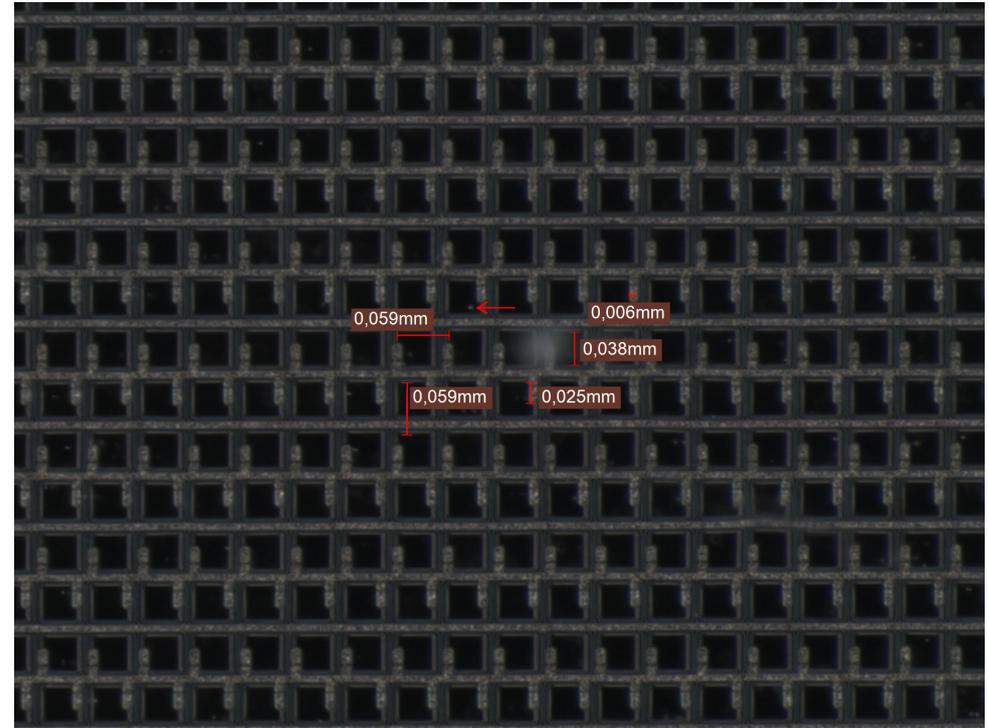
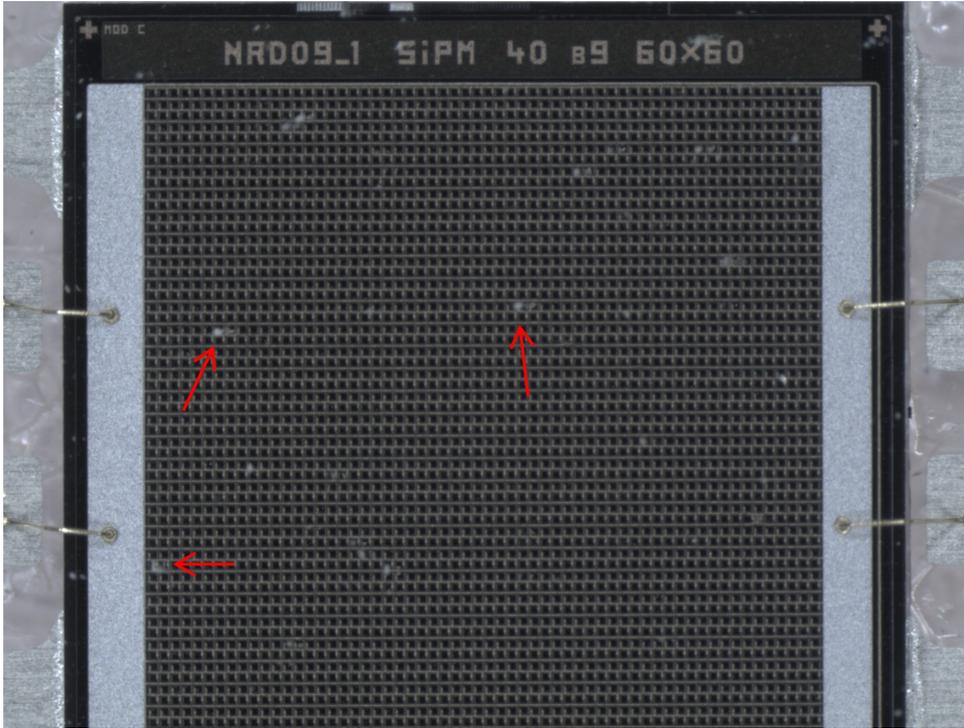
- Hamamatsu 1x1 mm<sup>2</sup>:
- 100 micron pitch
  - ~ 88 micron cell size

# STM SiPM PROTOTYPES: Mod A



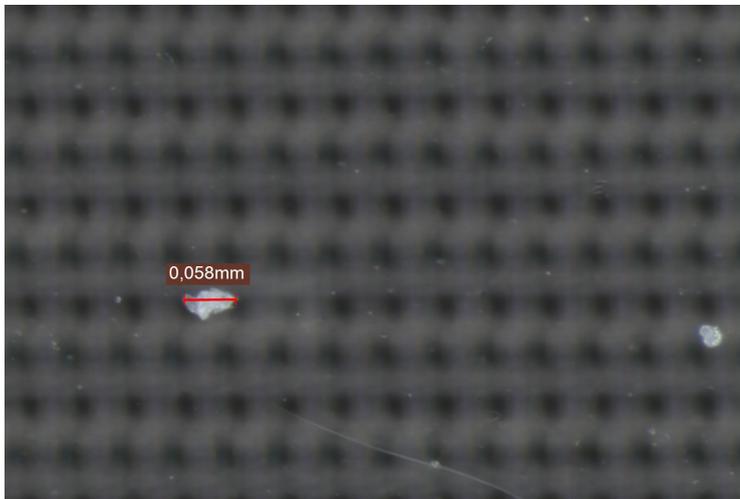
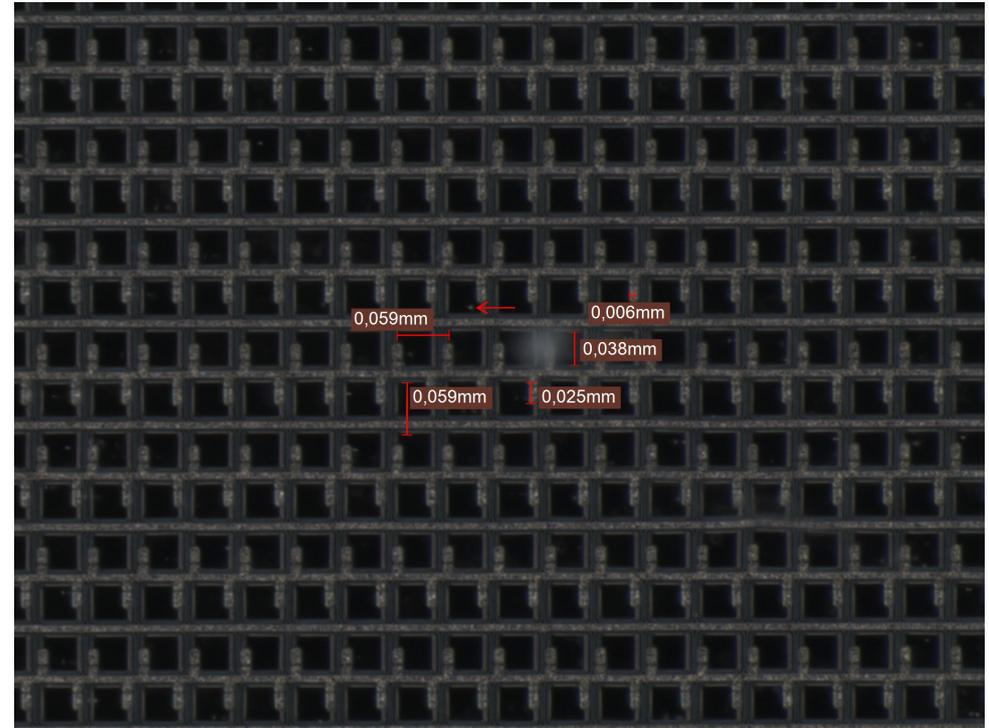
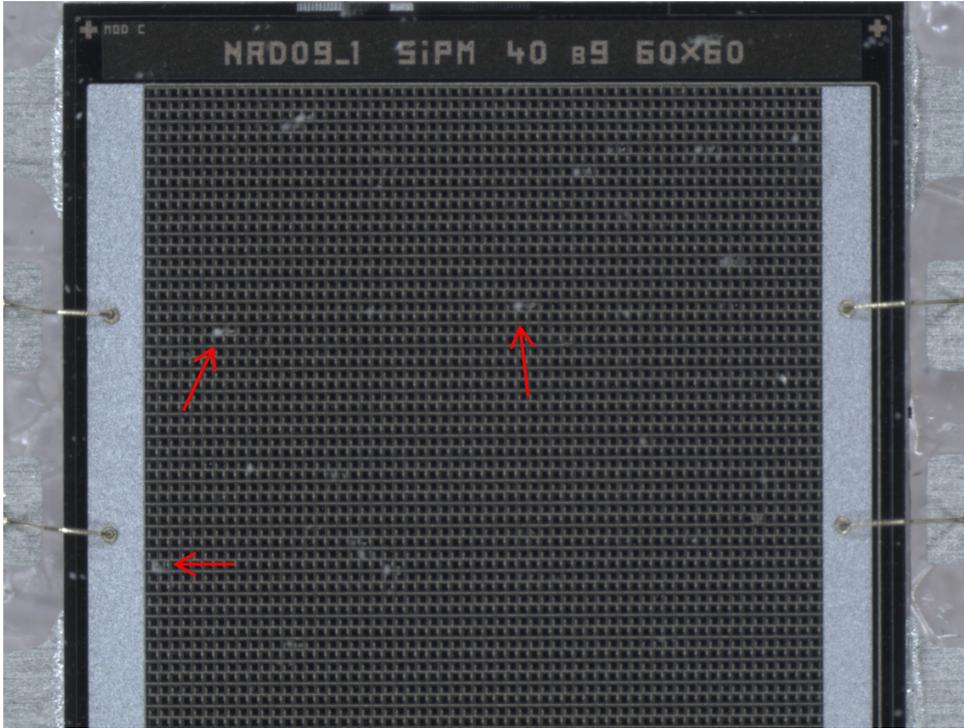
- Die Size: 4.37mmx4.37mm
- Array Size: 3.5mmx3.5mm
- # of cells: 70x70
- Pitch 50 micron
- Fill factor: 36% (~30% from pic)
- Some **dirt** on top, handling after production, **cleaning** → **removal**

# New STM SiPM PROTOTYPES: Mod C



- Die Size: 4.37mmx4.37mm
- Array Size: 3.5mmx3.5mm
- # of cells: 60x60
- Pitch 58 micron
- Fill factor: 45% (~37% from pic)
- Some dirt on top, handling after production, **cleaning** → **removal**

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# SiPM Characteristics measured

Single SiPM:

- Gain vs (  $V_{op}$  ; T )
- Linearity ( laser & rad. sources )
- Timing resolution (  $V_{op}$  ; T ; threshold )

2 SiPM PET:

- Energy resolution vs (  $V_{op}$  ; T )
- Back to back Timing resolution vs (  $V_{op}$  ; T ; threshold )

## SiPM: Single and PET Setups

### ● Gain & Intrinsic Timing:

- Laser set to single Photon level (neutral density filters)
- Single SiPM from STM (# 3)

### ● PET Setup:

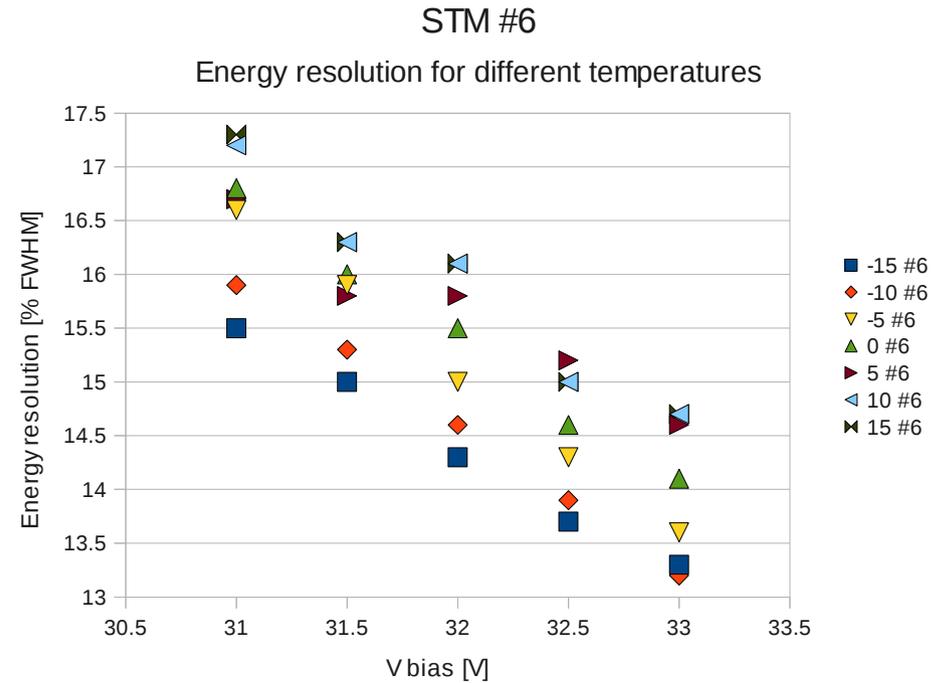
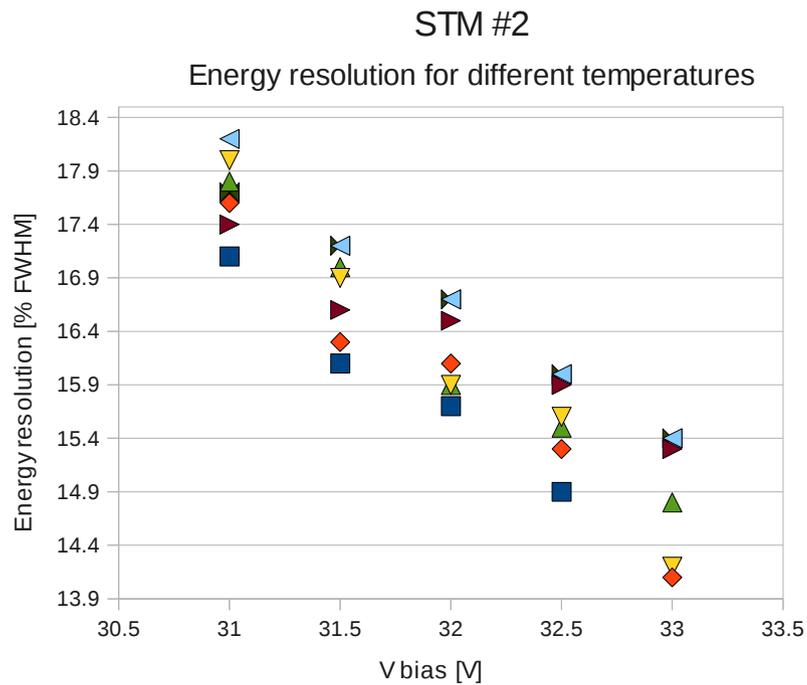
- 2 SiPMs with Saint-Gobain LYSO
- OR trigger

### ● Freezer:

- Temperature control
- Range:  $-15^{\circ}\text{C} \rightarrow 20^{\circ}\text{C}$



# Energy resolution: #2 & #6

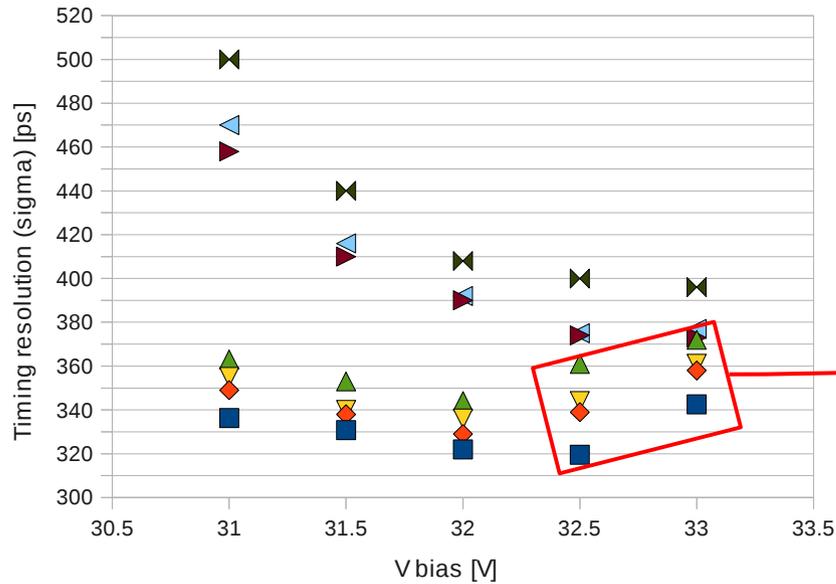


- Only minor improvement by lowering the temperature (related to improvement of gain by lowering temperature?)
- Energy resolution improves with increase of V
- STM #6 has a higher gain than #2

# BtB timing resolution: #2 & #6

## BtB Timing

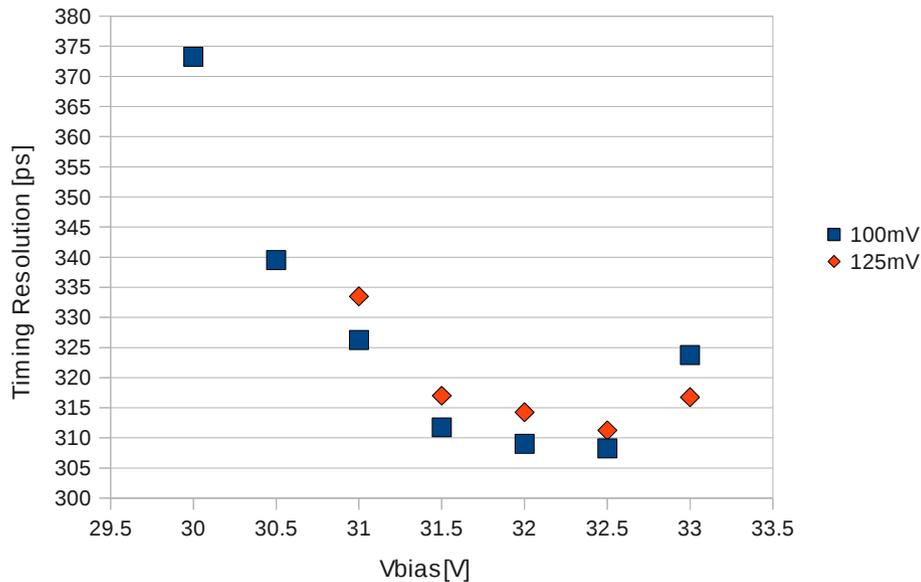
Timing resolution for different temperatures

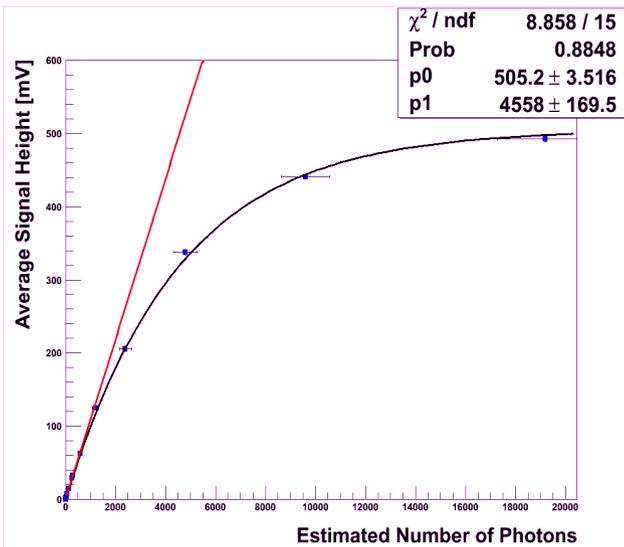


• Threshold ~ 150mV  
• At higher  $V_{bias}$  noise triggers too much and degrades time res.

• Threshold ~ 300mV

BtB Timing Resolution vs threshold  
equal gain, same threshold





## Linearity

### • Setup:

- Laser pulses (635nm)
- # of photons controlled with neutral density filters (going from 1 photon to ~ 20000 photons / pulse)
- Uniform light distribution over surface

Fitfunction  $\rightarrow y = p0 \cdot (1 - \exp(-x/p1))$

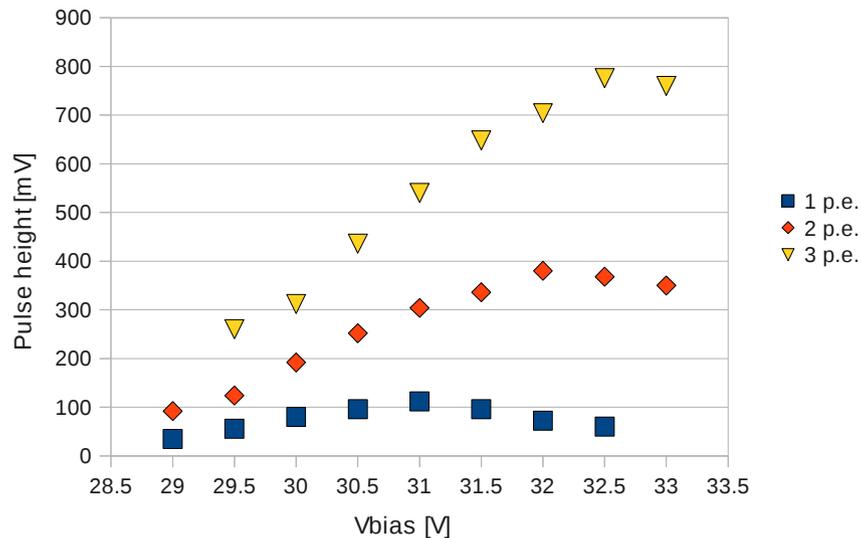
Line  $\rightarrow y = 0.109 \cdot x - 0.118$

## Low light intensity

Signal saturates with increasing  $V_{\text{bias}}$

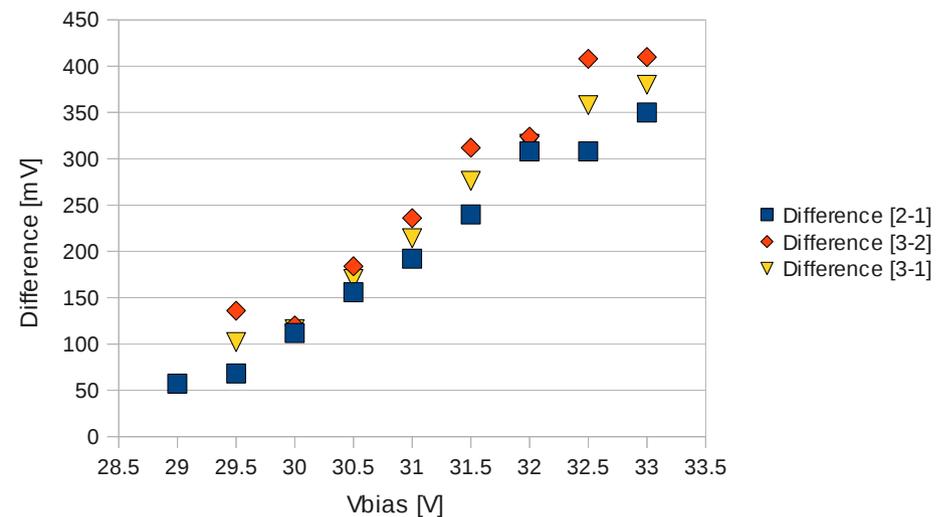
STM SiPM 3

neg. Vbias vs signal

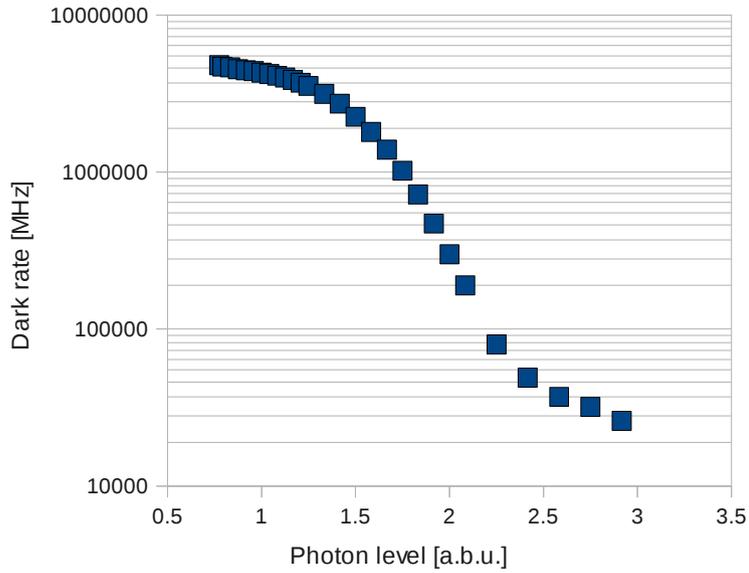


Differences in signal between single, double and triple photo-electrons behaves linear

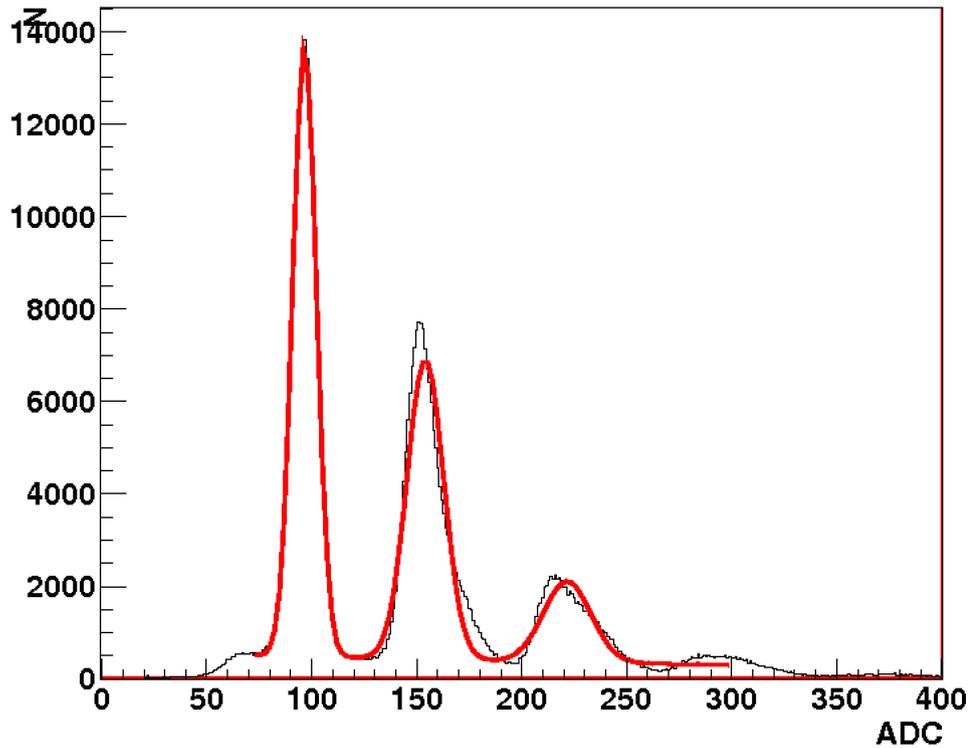
Pulse Height Differences



Dark rate vs. Threshold

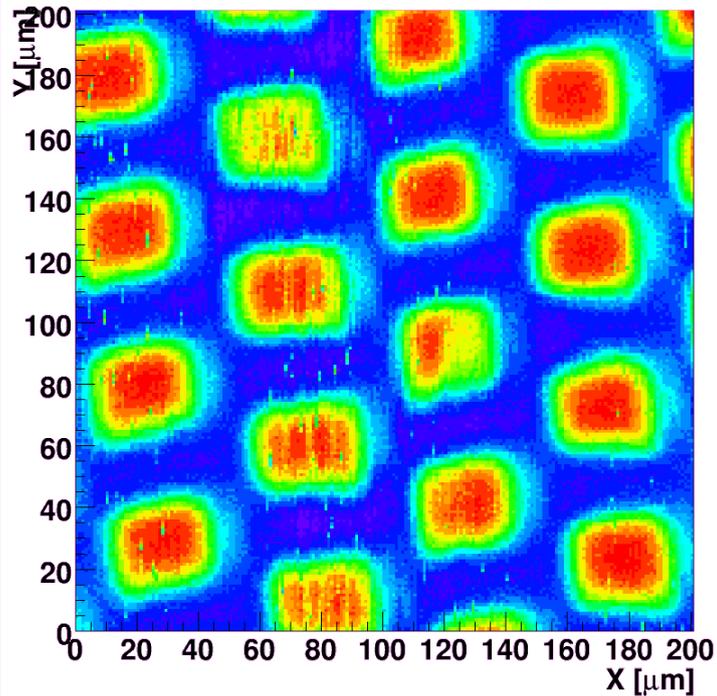


V\_bias = 29.5V Bgr= 97 p.e.1=154 p.e.2=222 gain1=1.60e+05 gain2=1.74e+05

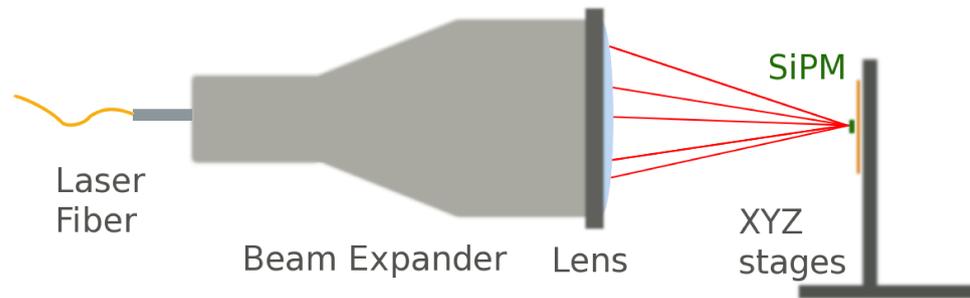


- Gain is  $\sim 1.67e5$   
Gain = average of gain calculated from 1 p.e. and 2 p.e.
- ADC has 25fC/count
- Amplification factor is 450

XY Position Scan Time Cut



## Position Scans



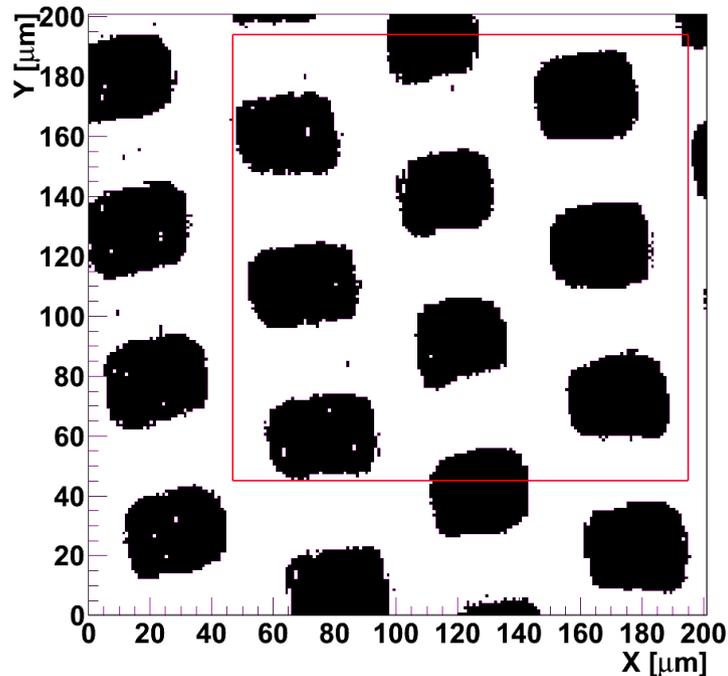
Setup:

- Pulsed laser (635 nm)
- Single Photon light intensity
- Sigma laser focal point  $\sim 4\text{-}5\ \mu\text{m}$
- $1\ \mu\text{m}$  stepsize (XYZ stages)

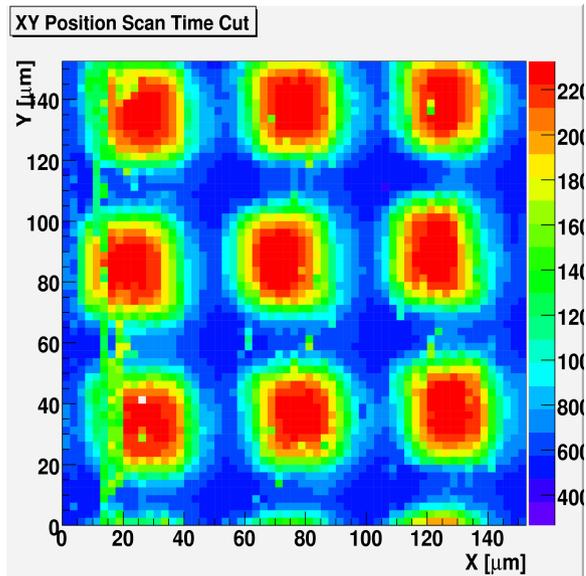
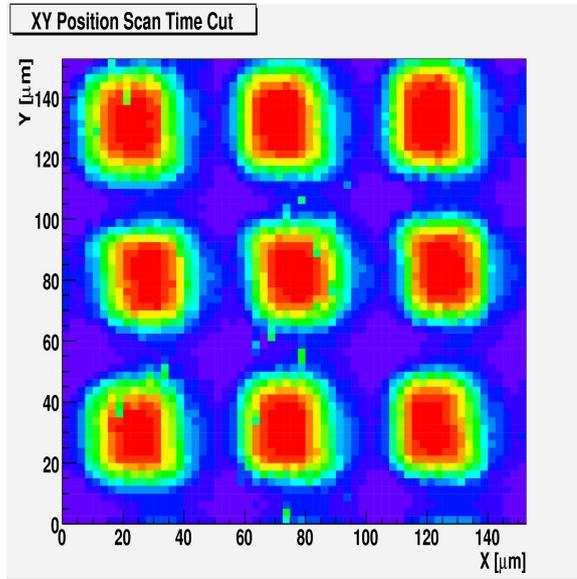
Geometrical factor:

- Color picture  $\rightarrow$  Black & White:
  - Value above 50% of max value  $\rightarrow$  count pixel as within active area (Black area)
  - Value below 50% max value  $\rightarrow$  pixel is outside active area (White Area)
- Geometrical factor result from total scan area is  $\sim 32.9\%$
- Geometrical factor result from red square area is  $\sim 33.0\%$

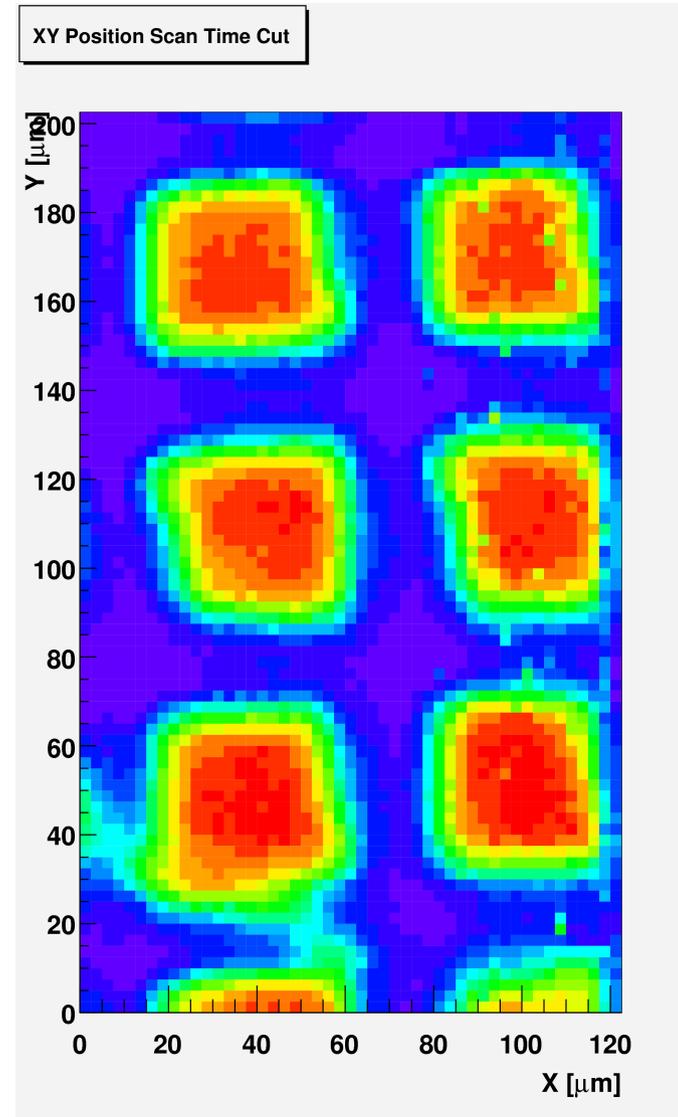
XY Position scan: total area eff. = 32.9%, red square geo. eff. = 33.0%



# new STMicroelectronics SiPM Model A



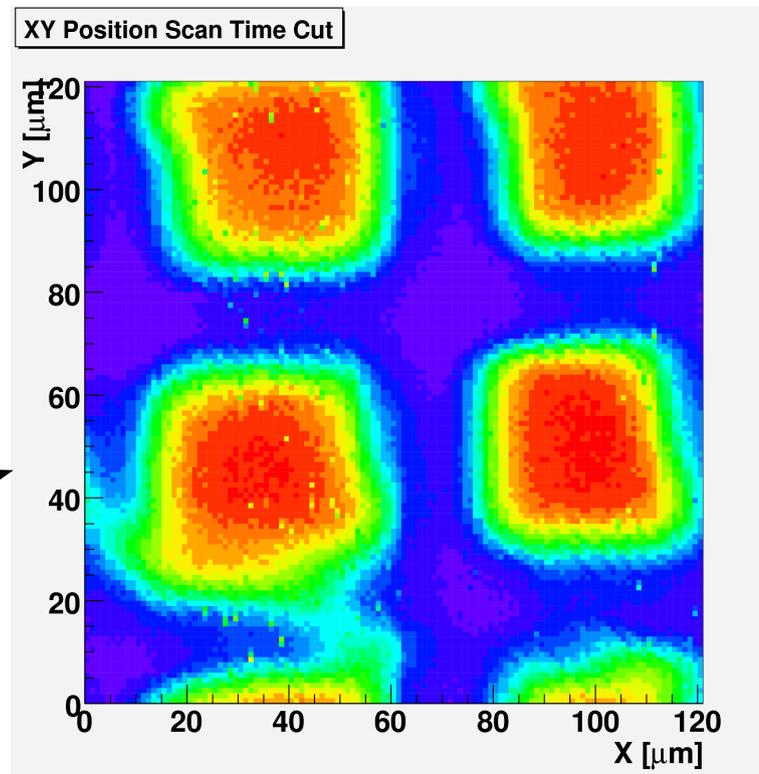
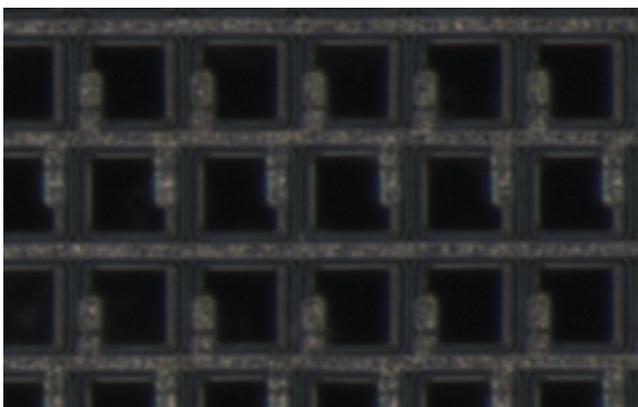
# new STMicroelectronics SiPM Model C



# new STMMicroelectronics SiPM

2D scans:

- Mod C 1micron step  $\rightarrow$
- Mod A 2x2.5 Micron step at different locations  $\rightarrow$  behaviour is fairly uniform



## Gain STMMicroelectronics SiPM for T = 15C $\rightarrow$ -20C

